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IDS - 0998/96 Number: 081468-0309196 Client Reference: P-1851.000-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

n Re the Application of

KOLESNYCHENKO et al.

'Group Art Unit: 1756

Application No.: 10/823,777

Examiner: Unassigned

Filed: April 14, 2004

Confirmation No.: 4703

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

September 8, 2004

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
KG	DE SMIT (081468-0309173)	10/820,227	04/08/2004	☑ Specification☑ Drawings☑ Other: stamped receipt card
	DE SMIT (081468-0309978)	10/860,662	06/04/2004	☒ Specification☒ Drawings☒ Other: stamped receipt card
	DUINEVELD et al. (081468-0308101)	10/773,461	02/09/2004	☒ Specification☒ Drawings☒ Other: stamped receipt card
	FLAGELLO et al. (081468-0302644)	10/698,012	10/31/2003	☒ Specification☒ Drawings☒ Other: stamped receipt card
	DE SMIT et al. (081468-0306530)	10/705,804	11/12/2003	☑ Specification☑ Drawings☑ Other: stamped receipt card
	LOF et al. (081468-0306781)	10/705,805	11/12/2003	☑ Specification☑ Drawings☑ Other: stamped receipt card
	LOF et al. (081468-0306524)	10/705,783	11/12/2003	☑ Specification☑ Drawings☑ Other: stamped receipt card

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Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
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6 STON WE KG	VAN SANTEN et al. (081468-0307331)	10/743,271	12/23/2003	☒ Specification☒ Drawings☒ Other: stamped receipt card
TRADEN	MULKENS et al. (081468-0307333)	10/743,266	12/23/2003	☒ Specification☒ Drawings☒ Other: stamped receipt card
	DERKSEN et al. (081468-0306526)	10/705,785	11/12/2003	 ☑ Specification ☑ Drawings ☑ Other: stamped receipt card
	SIMON et al. (081468-0307087)	10/724,402	12/01/2003	 ✓ Specification ✓ Drawings ✓ Other: stamped receipt card
	BLEEKER (081468-0306527)	10/715,116	11/18/2003	 ✓ Specification ✓ Drawings ✓ Other: stamped receipt card
	STREEFKERK et al. (081468-0306882)	10/719,683	11/24/2003	 ✓ Specification ✓ Drawings ✓ Other: stamped receipt card
	LOF et al. (081468-0306525)	10/705,816	11/12/2003	✓ Specification✓ Drawings✓ Other: stamped receipt card
	DIERICHS (081468-0308270)	10/775,326	02/11/2004	 ✓ Specification ✓ Drawings ✓ Other: stamped receipt card
	LOF et al. (081468-0309957)	10/857,614	06/01/2004	 ✓ Specification ✓ Drawings ✓ Other: stamped receipt card
	SUWA et al. (Reissue Application of U.S. Patent No. 6,191,429 B1)	10/367,910	02/19/2003	 ✓ Specification ✓ Drawings ✓ Other: stamped receipt card
V	ZAAL et al. (081468-0309012)	10/814,815	04/01/2004	✓ Specification✓ Drawings✓ Other: stamped receipt card

^{*}The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

PLEASE DO NOT PRINT the above information on the patent which results from this application.

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FORM PTO-1449 (modified) Atty. M# Client Ref. To: U.S. Department of Commerce Dkt. No. (PW FORM PAT-1449) SEP 0 8 2004 Patent and Trademark Office 309196 P-1851.000-US INFORMATION DISCLOSURE STATEMENT Applicant: KOLESNYCHENKO et al. BY APPLICANT Appln. No. 10/823,777 Filing Date: April 14, 2004 Page Group Art Unit: 1756 2851 Date: September 8, 2004 Examiner: Unknown U.S. PATENT DOCUMENTS Examiner's Document Date Name Class Sub Filing Date Initials* Number MM/YYYY (Family Name of First Inventor) Class (if appropriate) 04/1971 KG AR 3,573,975 DHAKA et al. 117 212 03/1972 BR 3,648,587 **STEVENS** 95 44 CR 4,346,164 08/1982 TABARELLI et al. 430 311 DR 4,390,273 06/1983 LOEBACH et al. 355 125 08/1983 326 ER 4.396,705 AKEYAMA et al. 430 11/1984 355 FR 4,480,910 TAKANASHI et al. 30 4,509,852 04/1985 GR TABARELLI et al. 355 lзо HR 5,040,020 08/1991 RAUSCHENBACH et al. 355 53 IR 5,121,256 06/1992 CORLE et al. 359 664 JR 5,610,683 03/1997 TAKAHASHI 355 53 KR 5,715,039 02/1998 FUKUDA et al. 355 53 LR 5,825,043 250 10/1998 SUWA 548 MR |5,900,354 05/1999 BATCHELDER 430 395 NR 6,191,429 02/2001 SUWA 250 548 FOREIGN PATENT DOCUMENTS English Abstract Translation Readily Document Date Country Inventor Name Available MM/YYYY Number Enclosed No Enclosed KG OR WO 99/49504 09/1999 PCT FUKAMI et al. X X PR EP 0023231 02/1981 **EUROPE** TABARELLI et al. Х QR EP 0418427 03/1991 **EUROPE** MIYAKE Х X RR EP 1039511 09/2000 **EUROPE** MURAKAMI et al. Х X SR DD 224448 07/1985 **GERMANY** HESSE et al. Х TR DD 242880 02/1987 **GERMANY** KUCH Х UR FR 2474708 07/1981 FRANCE LETELLIER Х JP 62-065326 03/1987 **JAPAN** VR MORIUCHI Х WR JP 62-121417 **JAPAN** 06/1987 NAKAZAWA Х XR JP 63-157419 06/1988 **JAPAN** NAKASUJI Х YR JP 04-305915 10/1992 **JAPAN** OZEKI et al. Х ZR JP 04-305917 10/1992 **JAPAN** OZEKI et al. х AAR JP 06-124873 JAPAN 05/1994 TAKAHASHI Х X OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.) BBR M. SWITKES et al., "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, KG December 17, 2001 CCRM. SWITKES et al., "Immersion Lithography at 157 nm", J. Vac. Sci. Technol: B., Vol. 19, KG No. 6, November/December 2001, pp. 2353-2356 DDR M. SWITKES et al., "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, KG September 4, 2002 Examiner <u>/Kevin Gutierrez/</u> Date Considered: 02/13/2007 *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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Complete if Known Substitute for form 1449A/PTO Application Number 10/823,777 Filing Date INFORMATION DISCLOSURE 04/14/2004 First Named Inventor STATEMENT BY APPLICANT ALEKSEY KOLESNYCHENKO Art Unit 1758 2851 Examiner Name Unassigned Gutierrez, (Use as many sheets as necessary) Attorney Docket Number 081468-0309196 of

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Examiner Signature	/Kevin Gutierrez/	Date Considered	02/13/2007

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered, include copy of this form with next communication to applicant. Applicant's unique citation designation number (optional), 2 See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04, 3 Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3), 4 For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. Skind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. Applicant is to place a check mark here if English language Translation is attached.

This collection of information is required by 37 CFR 1.97 and 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.